

OptiMOS[™]3 Power MOS Transistor Chip

| Туре | V(BR)DSS | R _{DS(on)} | Die size | Thickness |
|------------|----------|---------------------|----------------------------|-----------|
| IPC26N12NR | 120 V | 4.8 m $\Omega^{2)}$ | 6.0 * 4.36 mm ² | 250 μm |

DESCRIPTION

- N-channel enhancement mode
- For additional characteristic and max ratings refer to the datasheet of IPP048N12N3 G¹⁾
- AQL 0.65 for visual inspection according to failure catalogue
- Electrostatic Discharge Sensitive Device according to MIL-STD 883C
- Die bond: soldered or glued
- Backside metallization: NiV system
- Frontside metallization: AISi system
- Passivation: nitride (only on edge structure)

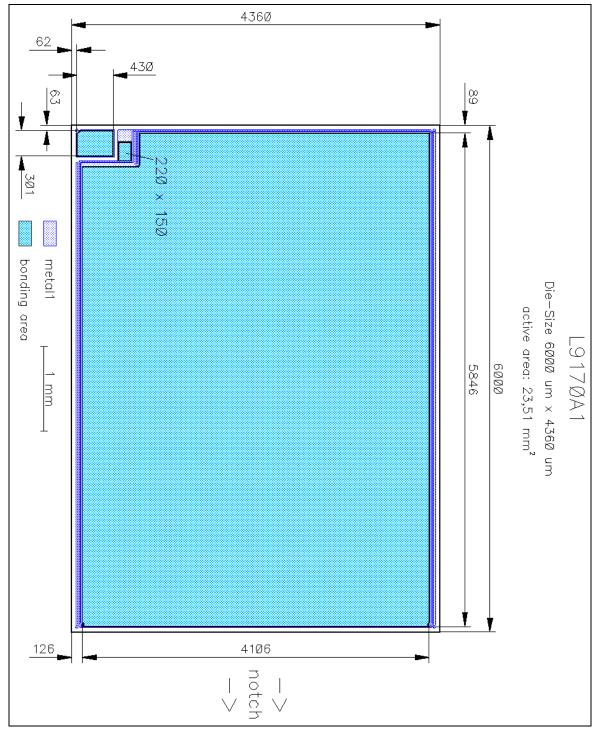
Electrical Characteristics on Wafer Level

at $T_j = 25 \text{ °C}$, unless otherwise specified.

| Parameter | Symbol | Value | | | Unit | Conditions |
|----------------------------------|---------------------|-------|-------------------|-------------------|------|--|
| | | min. | typ. | max. | | |
| Drain-source breakdown voltage | V(BR)DSS | 120 | - | - | V | $V_{GS} = 0V$ |
| | | | | | | I _D = 1 mA |
| Gate threshold voltage | V _{GS(th)} | 2 | - | 4 | V | $V_{DS} = V_{GS}$ |
| | | | | | | I _D = 230 μA |
| Zero gate voltage drain current | I _{DSS} | - | 0.1 | 1 | μA | $V_{GS} = 0V$ |
| | | | | | | V _{DS} = 100 V |
| Gate-source leakage current | I _{GSS} | - | 1 | 100 | nA | V _{GS} = 20 V |
| | | | | | | $V_{DS} = 0 V$ |
| Drain-source on-resistance | R _{DS(on)} | - | 3.2 ⁴⁾ | 100 ³⁾ | mΩ | V _{GS} = 10 V |
| | | | | | | I _D = 2.0 A |
| Reverse diode forward on-voltage | V _{SD} | - | 1.0 | 1.2 | V | V _{GS} =0 V |
| | | | | | | I _F = 1 A |
| Internal gate resistance | R _G | - | 2 | - | Ω | |
| Additional gate resistor | R _{Gadd} | | 16 | | Ω | |
| Avalanche energy, single pulse | E _{AS} | - | 45 ⁵⁾ | - | mJ | I _D = 30 A, <i>R</i> _{GS} =25Ω |



Chip-Layout:



¹⁾ IPP048N12N3 G dynamic characterization does not include the internal added Rg

²⁾ packaged in a P-TO220-3-1 (see ref. product)

³⁾ limited by wafer test-equipment

 $^{\rm 4)}$ typical bare die $R_{\rm DS(on)};\,V_{\rm GS}{=}10V$

⁵⁾ Wafer tested. For general avalanche capability refer to the datasheet of IPP048N12N3 G

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